

**Please delete the present Abstract of the Disclosure and replace it with the following new Abstract of the Disclosure.**

A film-forming device with a substrate rotating mechanism, ~~comprises:~~ includes a susceptor (30) in the form of a circular disk; a base plate (6) positioned below the susceptor (30) and rotatably retaining the susceptor (30); a revolution generating section (5) rotating the susceptor (30) at the outer periphery of the susceptor (30); a plurality of substrate tray retaining sections (23) arranged on the susceptor (30); a plurality of annular substrate trays (20) rotatably supported in the corresponding substrate tray retaining sections (23); a rotation generating section (4) rotating the substrate trays (20); and a plurality of substrates (W) retained in the substrate trays (20). The substrates (W) are revolved by the rotation of the susceptor (30) and rotated by the rotation of the substrate trays (20) to apply a certain film-forming process. The substrates (W) are rotated and revolved by one or more revolution generating section (5) and the rotation generating section (4).